



Supporting Information

for *Small*, DOI: 10.1002/sml.201603574

GaP/GaN_P Heterojunctions for Efficient Solar-Driven Water Oxidation

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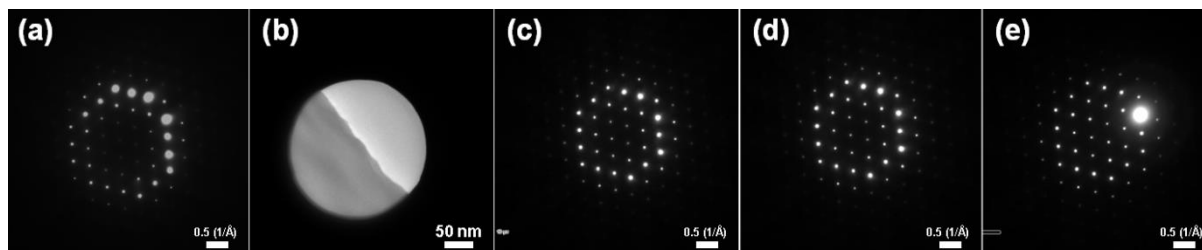


Figure S1. Selected area electron diffraction (SAED) pattern of (a) an area of n-GaP, (c) an area including both i-GaNP and p⁺-GaP layers (TEM image of selected region is shown in (b)), and (d) i-GaNP and (e) p⁺-GaP of selected areas in (b). The combined SAED pattern (Figure S1c) is very similar to the SAED pattern of i-GaNP (Figure S1d) and p⁺-GaP (Figure S1e).

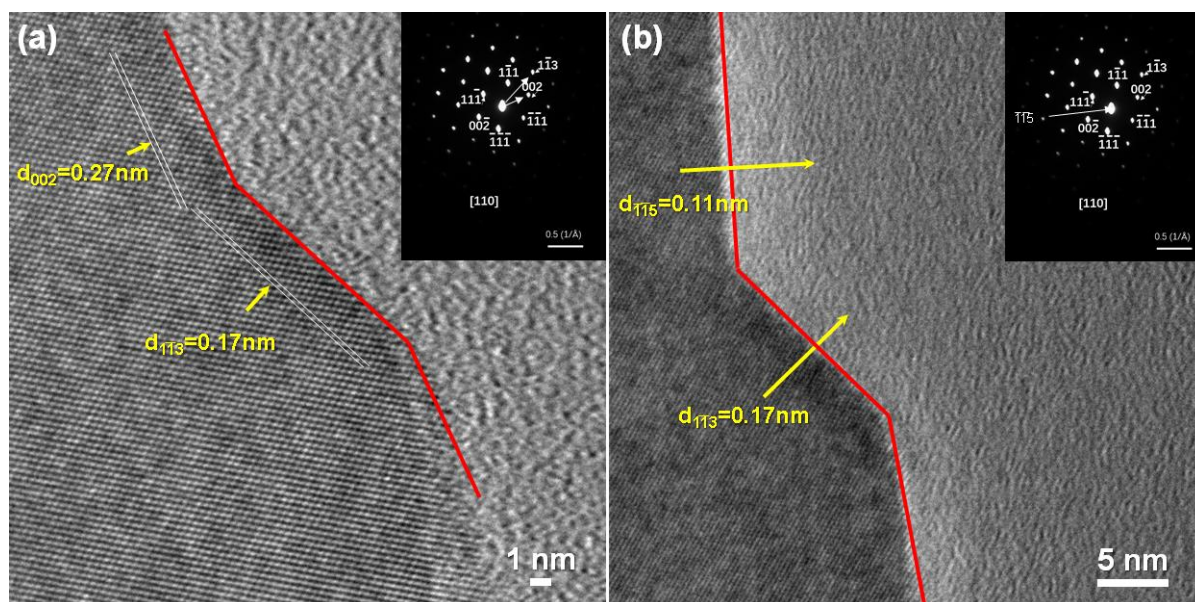


Figure S2. (a,b) HRTEM images of surface structure of n-GaP/i-GaNP/p⁺-GaP thin film substrate with the identified facets.

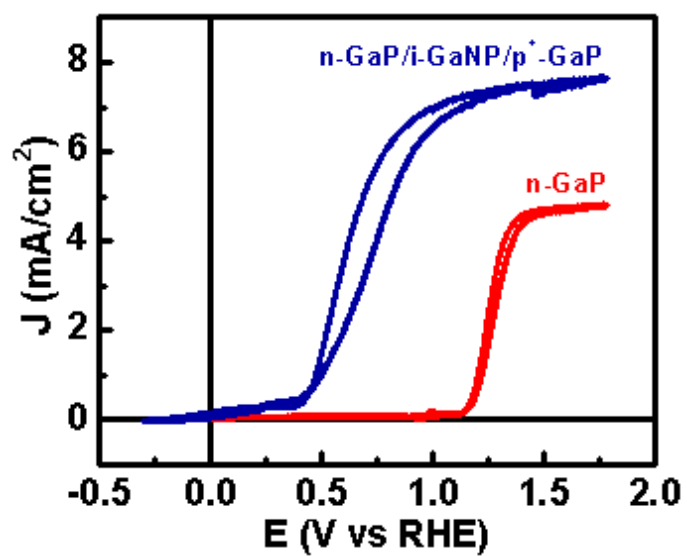


Figure S3. Cyclic voltammetry (CV) measurement under illumination of the TiO₂/Ni-coated n-GaP and n-GaP/i-GaNP/p⁺-GaP thin film heterojunction substrates recorded at a scan rate of 10 mV/s in 1 M KOH electrolyte.

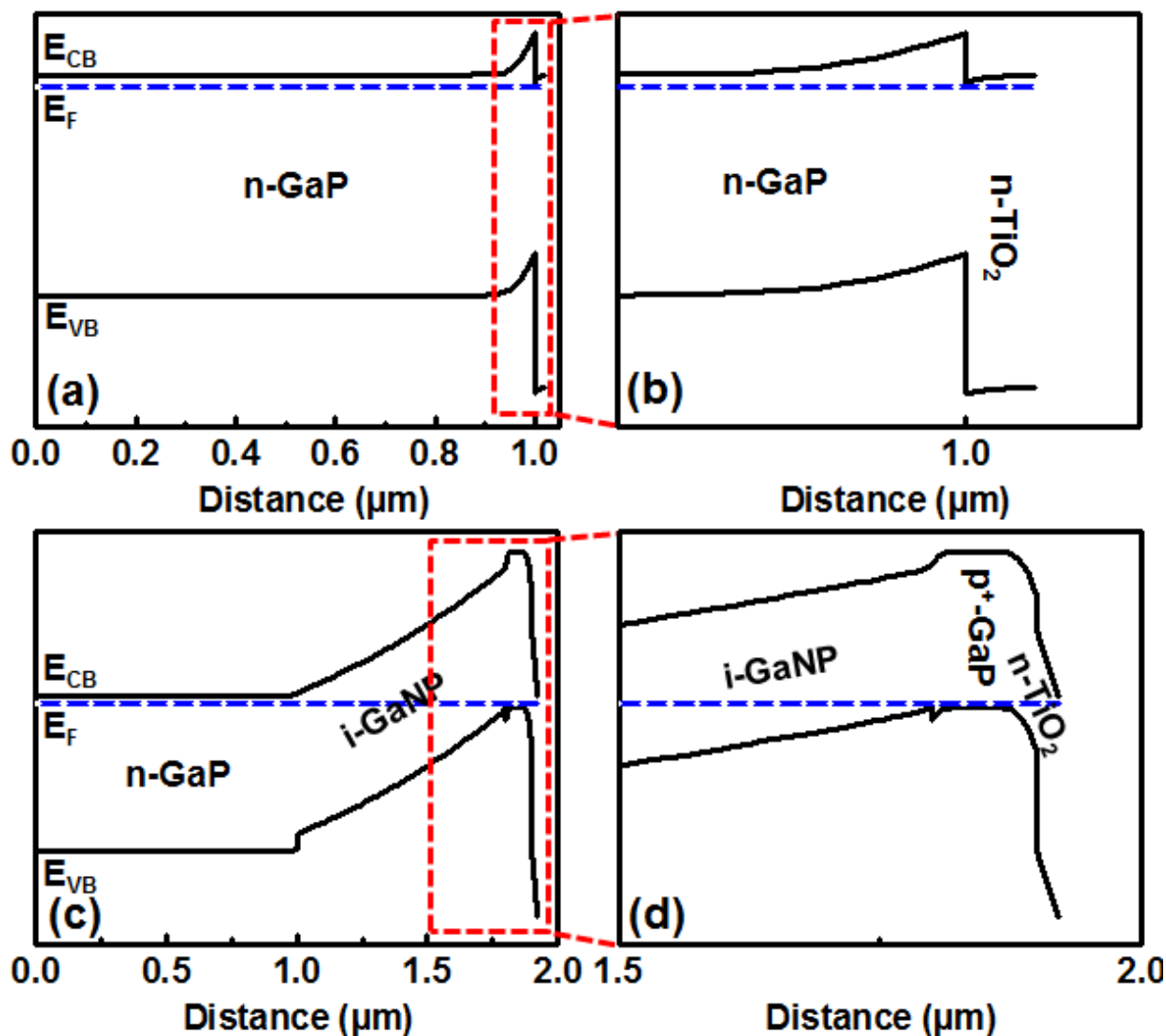


Figure S4. Approximate energy band diagram of the TiO₂-coated (a,b) n-GaP and (c,d) n-GaP/i-GaNP/p⁺-GaP substrates at equilibrium condition and at dark, which was simulated using SCAPS (version 3.1.02) numerical simulation software. The band gap of anatase TiO₂ layer deposited by ALD was considered to be 3.2 eV.^[1,2] The electron affinity of TiO₂ (anatase and ALD deposited) was considered as ~4.3 eV.^[1,3] The doping concentration of the ALD-deposited anatase TiO₂ is in the range of 10^{17} cm^{-3} [4] (was considered 10^{17} in the simulation). The considered TiO₂ thickness was 20 nm based on its deposited thickness.

References

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